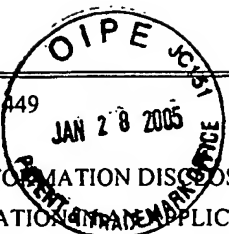








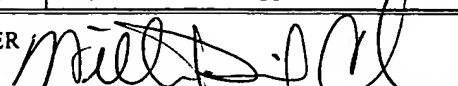
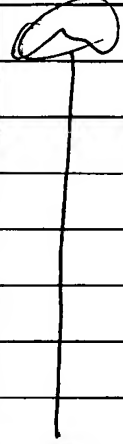



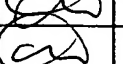


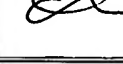

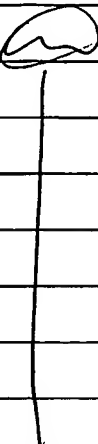



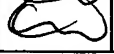



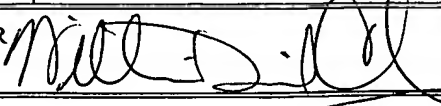
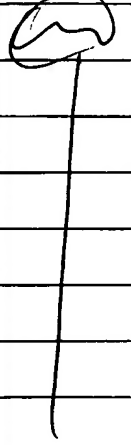







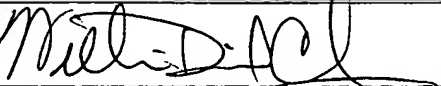



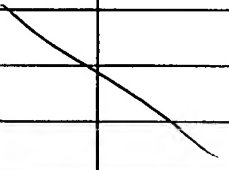


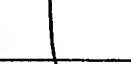









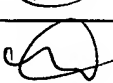

FORM PTO-1449 		DOCKET NUMBER DSI 303	APPLICATION NUMBER 10/816,179 10/815,994				
APPLICANTS Chung J. Lee and Atul Kumar		FILING DATE March 31, 2004	GROUP ART UNIT 1763 2823				
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INFORMATION DISCLOSURE CITATION IN AN APPLICATION		APPLICANTS Chung J. Lee and Atul Kumar					
		FILING DATE March 31, 2004		GROUP ART UNIT 4763 2823			
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		FILING DATE March 31, 2004		GROUP ART UNIT 1763 2823			
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SHEET 1 OF 1

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	APPLICANTS Chung J. Lee and Atul Kumar	
	FILING DATE March 31, 2004	GROUP ART UNIT 2827

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